

L Number	Hits	Search Text	DB	Time stamp
-	0	"20020157068"	USPAT	2004/05/06 11:19
-	1	"20020157068"	USPAT; US-PGPUB	2004/05/06 15:34
-	1	"05206219"	JPO	2004/05/06 11:19
-	472	(opc or optical near process near correction) and photolithography and mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/10 18:16
-	44	((opc or optical near process near correction) and photolithography and mask) and hierarchy	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/06 16:01
-	472	(opc or optical near process near correction) and photolithography and (mask or reticle near writ\$3 near (tool or device))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/06 16:00
-	44	((opc or optical near process near correction) and photolithography and (mask or reticle near writ\$3 near (tool or device))) and hierarchy	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/06 16:03
-	22	((opc or optical near process near correction) and photolithography and (mask or reticle near writ\$3 near (tool or device))) and hierarchy) and (reduc\$3 or decreas\$3 or eliminat\$3) with data	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/10 15:25
-	19	((opc or optical near process near correction) and photolithography and (mask or reticle near writ\$3 near (tool or device))) and hierarchy) and (reduc\$3 or decreas\$3 or eliminat\$3) with data	USPAT; JPO; DERWENT	2004/05/10 15:26
-	2	((opc or optical near process near correction) and photolithography and (mask or reticle near writ\$3 near (tool or device))) and hierarchy) and (reduc\$3 or decreas\$3 or eliminat\$3) with data) and (cop\$3 or transfer\$3) with cell	USPAT; JPO; DERWENT	2004/05/10 15:30
-	2	((opc or optical near process near correction) and photolithography and (mask or reticle near writ\$3 near (tool or device))) and hierarchy) and (reduc\$3 or decreas\$3 or eliminat\$3) with data) and (cop\$3 or transfer\$3) with cell	USPAT; JPO; DERWENT	2004/05/10 15:30
-	14	716/11 and (opc or optical near process near correction) and photolithography and mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/10 18:17
-	160	716/19 and (opc or optical near process near correction) and photolithography and mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/05/10 18:17